

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

PATENT APPLICATION

Inventor(s): GROENEVELD et al.
 Appln. No.: 09 758,172
 Series Code ↑ Serial No. ↑
 Filed: January 12, 2001
 Hon. Commissioner of Patents
 Washington, D.C. 20231



Group Art Unit 2881
 Examiner: SOUW, BERNARD
 Atty. Dkt. P 276593 | P-0165.010-US
 M# Client Ref
 Appln. Title: ABBE ARM CALIBRATION SYSTEM
 FOR USE IN A LITHOGRAPHIC
 APPARATUS

Sir:

REPLY/AMENDMENT/LETTER

Date: March 5, 2003

This is a reply/amendment/letter in the above-identified application and includes the herewith attachment of same date and subject which is incorporated herein by reference and the signature below is treated as the signature to the attachment in absence of a signature thereto.

FEE REQUIREMENTS FOR CLAIMS AS AMENDED

1. Small Entity claim A. <input checked="" type="checkbox"/> NOT made B. <input type="checkbox"/> Withdrawn C. <input type="checkbox"/> made herewith D. <input type="checkbox"/> made previously For B & C See Required Separate Paper (Pat-256)		Claims remaining after amendment	Highest number previously paid for	Present Extra	Large/Small Entity	Additional Fee	Fee Code Lg/Sm
2. Total Effective Claims		20	**minus 20	0	x \$18/\$9 =	+ \$0	103/203
3. Independent Claims		3	***minus 3	0	x \$84/\$42 =	+ \$0	102/202
4. If amendment enters proper multiple dependent claim(s) into this application for first time (leave blank if this is a reissue application)					add	+ \$280/\$140 =	+ \$0 104/204
5. Original due Date: February 21, 2003		<input type="checkbox"/> NONE					
6. Petition is hereby made to extend the original due date to cover the date this response is filed for which the requisite fee is attached		(1 mo)	\$110/\$55 =				115/215
		(2 mos)	\$410/\$205 =		+ \$110		116/216
		(3 mos)	\$930/\$465 =				117/217
		(4 mos)	\$1,450/\$725 =				118/218
		(5 mos)	\$1,970/\$985 =				128/228
7. Enter any previous extension fee paid since above original due date and subtract					- \$0		
8. Extension Fee					+ \$110		
9. If Terminal Disclaimer attached, add Rule 20(d) official fee					+ \$110/\$55	+ \$0	148/248
10. If IDS attached requires Official Fee under Rule 97 (c),					+ \$180	+ \$0	126
or if Rule 97(d) Request					+ \$180		126
11. After-Final Request Fee per rules 129(a) and 17(r)					+ \$750/370	+ \$0	146/246
12. No. of additional inventions for examination per Rule 129(b)					x \$750/375 ea	+ \$0	149/249
13. Request for Continued Examination (RCE)					+ \$750/375	+ \$0	1179/1279
14. Petition fee for					+ \$0		
TOTAL FEE =						\$110	
PLEASE CHARGE OUR DEP. ACCT							

15. 16. *If the entry in this space is less than entry in next space, the "Present Extra" result is "0".
 17. **If the "Highest number previously paid for" in this space is less than 20, write "20" in this space.
 18. ***If the "Highest number previously paid for" in this space is less than 3, write "3" in this space.

Our Deposit Account No. 03-3975)
 (Our Order No. 81468 276593
 C# M#

CHARGE STATEMENT: The Commissioner is hereby authorized to charge any fee specifically authorized hereafter, or any missing or insufficient fee(s) filed, or asserted to be filed, or which should have been filed herewith or concerning any paper filed hereafter, and which may be required under Rules 16-18 (missing or insufficiencies only) now or hereafter relative to this application and the resulting Official Document under Rule 20, or credit any overpayment, to our Accounting/Order Nos. shown above, for which purpose a duplicate copy of this sheet is attached.

This CHARGE STATEMENT does not authorize charge of the issue fee until/unless an issue fee transmittal sheet is filed.

Query: Is appeal deadline now? If so, file Notice of Appeals separately.

03/37/2003 GWD00F1 00000062 033975 09758172

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NOTE: File this cover sheet in duplicate with PTO receipt (PAT-103A) and attachments



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION OF

Groeneveld *et al.*

Appln. No.: 09/758,172

Filed: January 12, 2001

Title: Abbe Arm Calibration System for Use in Lithographic Apparatus

Confirmation No.: 9375

Group Art Unit 2881

Examiner: SOUW, BERNARD

March 5, 2003

* * * * *

AMENDMENT

Hon. Commissioner of Patents
Washington, D.C. 20231

Sir:

In response to the Office Action dated November 21, 2002, please amend the above-identified application as follows:

IN THE SPECIFICATION:

Page 2, delete the whole paragraph starting in line 25 and replace it with the following new paragraph:

-- Lithographic projection apparatus can be used, for example, in the manufacture of integrated circuits (ICs). In such a case, the patterning means may generate a circuit pattern corresponding to an individual layer of the IC, and this pattern can be imaged onto a target portion (comprising one or more dies) on a substrate (silicon wafer) that has been coated with a layer of radiation-sensitive material (resist). In general, a single wafer will contain a whole network of adjacent target portions that are successively irradiated via the projection system, one at a time. In current apparatus, employing patterning by a mask on a mask table, a distinction can be made between two different types of machine. In one type of lithographic projection apparatus, each target portion is irradiated by exposing the entire mask pattern onto the target portion at once; such an apparatus is commonly referred to as a wafer stepper. In an